I . FENT COOPERATION TREA

		From the INTERNATIONAL BUREAU			
PCT	To:	То:			
NOTIFICATION OF THE RECORDING OF A CHANGE (PCT Rule 92bis.1 and Administrative Instructions, Section 422)	Qine IP Fo A4 B Ively Ham	BOWDERY, A.O. Qinetiq Limited IP Formalities A4 Bldg., Cody Technology Park Ively Road, Farnborough Hampshire GU14 0LX			
Date of mailing (day/month/year) 12 November 2001 (12.11.01)	HOY.	ROYAUME-UNI			
Applicant's or agent's file reference JL2428		IMPORTANT NOTI	FICATION		
International application No. PCT/GB00/00951	1	nal filing date (day/month/ye March 2000 (15.03.00)	ear)		
The following indications appeared on record concerning: X the applicant	the ager	nt the commo	on representative		
Name and Address THE SECRETARY OF STATE FOR DEFENCE		State of Nationality GB	State of Residence GB		
Defence Evaluation and Research Agency Farnborough		Telephone No.] 00		
Hampshire GU14 0LX United Kingdom		Facsimile No.			
		Teleprinter No.			
2. The International Bureau hereby notifies the applicant that the second secon	Ī				
X the person the name the ad	dress [the nationality	the residence		
Name and Address		State of Nationality	State of Residence		
QINETIQ LIMITED 85 Buckingham Gate		GB GB Telephone No.			
London SW1 6TD United Kingdom		Telephone No.			
Onited Kingdom		Facsimile No.			
		Teleprinter No.			
3. Further observations, if necessary:					
4. A copy of this notification has been sent to:					
X the receiving Office	Γ	the designated Offices of	concerned		
the International Searching Authority	Ī	X the elected Offices cond	erned		
X the International Preliminary Examining Authority		other:			
The International Bureau of WIPO	Authorized	officer			
34, chemin des Colombettes 1211 Geneva 20, Switzerland		R. Chrem			
Facsimile No : (41,22) 740 14 35	Telephone No.: (41-22) 338 83 38				

FIGENT COOPERATION TREA

	From the INTERNATIONAL BUREAU			
PCT	То:			
NOTIFICATION OF THE RECORDING OF A CHANGE (PCT Rule 92bis.1 and Administrative Instructions, Section 422) Date of mailing (day/month/year)	BOWDERY, A.O. Qinetiq Limited IP Formalities A4 Bldg., Cody Technology Park Ively Road, Farnborough Hampshire GU14 0LX ROYAUME-UNI			
12 November 2001 (12.11.01)				
Applicant's or agent's file reference JL2428	IMPORTANT NOTIFICATION			
International application No. PCT/GB00/00951	International filing date (day/month/year) 15 March 2000 (15.03.00)			
The following indications appeared on record concerning: the applicant	X the agent the common representative			
Name and Address BARKER BRETTELL 138 Hagley Road	State of Nationality State of Residence Telephone No.			
Edgbaston Birmingham B16 9PW United Kingdom	0121-456-1364 Facsimile No.			
	0121-456-1368 Teleprinter No.			
The International Bureau hereby notifies the applicant that X the person the name the ad	·			
Name and Address BOWDERY, A.O. Qinetig Limited	State of Nationality State of Residence			
IP Formalities	Telephone No. 44 01252 392710			
A4 Bldg., Cody Technology Park Ively Road, Farnborough	Facsimile No.			
Hampshire GU14 0LX United Kingdom	44 01252 393920			
	Teleprinter No.			
3. Further observations, if necessary:				
4. A copy of this notification has been sent to:				
X the receiving Office	the designated Offices concerned			
the International Searching Authority	X the elected Offices concerned			
X the International Preliminary Examining Authority	other:			
The International Bureau of WIPO	Authorized officer			
34, chemin des Colombettes 1211 Geneva 20, Switzerland	R. Chrem			
Facsimile No.: (41-22) 740.14.35	Telephone No.: (41-22) 338.83.38			

P/ NT COOPERATION TREAT

PCT

NOTIFICATION OF ELECTION

(PCT Rule 61.2)

From the INTERNATIONAL BUREAU

To:

Commissioner
US Department of Commerce
United States Patent and Trademark
Office, PCT
2011 South Clark Place Room
CP2/5C24
Arlington, VA 22202

Date of mailing (day/month/year) 08 December 2000 (08.12.00)	ETATS-UNIS D'AMERIQUE in its capacity as elected Office
International application No.	Applicant's or agent's file reference
PCT/GB00/00951	JL2428
International filing date (day/month/year)	Priority date (day/month/year)
15 March 2000 (15.03.00)	16 March 1999 (16.03.99)
Applicant	
WALLIS, David, John et al	

1.	The designated Office is hereby notified of its election made:
ĺ	X in the demand filed with the International Preliminary Examining Authority on:
	10 October 2000 (10.10.00)
	in a notice effecting later election filed with the International Bureau on:
2.	The election X was
	made before the expiration of 19 months from the priority date or, where Rule 32 applies, within the time limit under Rule 32.2(b).

The International Bureau of WIPO 34, chemin des Colombettes 1211 Geneva 20, Switzerland Authorized officer

Olivia TEFY

Telephone No.: (41-22) 338.83.38

(PCT Article 18 and Rules 43 and 44)

Applicant's or agent's file reference FOR FURTHER see Notification of Transmittal of International Search Report (Form PCT/ISA/220) as well as, where applicable, item 5 below.						
JL2428 International application No.	International filing date (day/month/year)	(Earliest) Priority Date (day/month/year)				
• •	international lining date (day/month/year)					
PCT/GB 00/00951	15/03/2000	16/03/1999				
Applicant						
THE SECRETARY OF STATE FO	R DEFENCE et al.					
This International Search Report has been according to Article 18. A copy is being tra	n prepared by this International Searching Aut Insmitted to the International Bureau.	hority and is transmitted to the applicant				
This International Search Report consists [X] It is also accompanied by	of a total of3 sheets. a copy of each prior art document cited in this	report.				
Basis of the report						
	international search was carried out on the ba ess otherwise indicated under this item.	sis of the international application in the				
the international search w Authority (Rule 23.1(b)).	as carried out on the basis of a translation of t	he international application furnished to this				
was carried out on the basis of the	e sequence listing :	nternational application, the international search				
	onal application in written form.					
1	ernational application in computer readable for	m.				
	this Authority in written form.					
	this Authority in computer readble form.					
	osequently furnished written sequence listing of s filed has been furnished.	loes not go beyond the disclosure in the				
the statement that the info furnished	ormation recorded in computer readable form i	is identical to the written sequence listing has been				
2. Certain claims were fou	nd unsearchable (See Box I).					
3. Unity of invention is lac	king (see Box II).					
4. With regard to the title,						
the text is approved as su	bmitted by the applicant.					
the text has been establis	hed by this Authority to read as follows:					
5. With regard to the abstract, X the text is approved as submitted by the applicant. The text has been established, according to Rule 38.2(b), by this Authority as it appears in Box III. The applicant may,						
within one month from the	e date of mailing of this international search re	port, submit comments to this Authority.				
6. The figure of the drawings to be pub		<u> </u>				
as suggested by the appl		None of the figures.				
because the applicant fai						
because this figure better	characterizes the invention.					

International Application No B 00/00951

A, CLASSIFICATION OF SUBJECT MATTER IPC 7 G01N23/20 G01N23/207

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

 $\begin{array}{ccc} \text{Minimum documentation searched (classification system followed by classification symbols)} \\ \text{IPC} & 7 & \text{G01N} \end{array}$

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal, WPI Data, PAJ, INSPEC

Category °	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
х	DD 270 770 A (FREIBERG BERGAKADEMIE) 9 August 1989 (1989-08-09)	1-4,6-8, 11-15, 18,23, 24,29, 30,32,33
A - Y	the whole document	6,28 37
Υ	US 5 414 747 A (RUUD CLAYTON O ET AL) 9 May 1995 (1995-05-09) cited in the application abstract	37
	-/	

X Further documents are listed in the continuation of box C.	Patent family members are listed in annex.
 Special categories of cited documents: "A" document defining the general state of the art which is not considered to be of particular relevance "E" earlier document but published on or after the international filing date "L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified) "O" document referring to an oral disclosure, use, exhibition or other means "P" document published prior to the international filing date but later than the priority date claimed 	"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention "X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone "Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art. "&" document member of the same patent family
Date of the actual completion of the international search	Date of mailing of the international search report
19 October 2000	25/10/2000
Name and mailing address of the ISA	Authorized officer
European Patent Office, P.B. 5818 Patentlaan 2 NL – 2280 HV Rijswijk Tel. (+31–70) 340–2040, Tx. 31 651 epo nl, Fax: (+31–70) 340–3016	Hulne, S

PO 00/00951

		PO 00/00951
C.(Continu	ation) DOCUMENTS CONSIDERED TO BE RELEVANT	
Category °	Citation of document, with indication,where appropriate, of the relevant passages	Relevant to claim No.
x ·	MAZUELAS A ET AL: "Strain compensation in highly carbon doped GaAs/AlAs distributed Bragg reflectors" JOURNAL OF CRYSTAL GROWTH,NL,NORTH-HOLLAND PUBLISHING CO. AMSTERDAM, vol. 175-176, no. 3001, 1 May 1997 (1997-05-01), pages 383-386, XP004091323 ISSN: 0022-0248 abstract	1,28
X	VELLING P ET AL: "InGaP/GaAs hole barrier asymmetry determined by (002) X-ray reflections and p-type DB-RTD hole transport" JOURNAL OF CRYSTAL GROWTH,NL,NORTH-HOLLAND PUBLISHING CO. AMSTERDAM, vol. 195, no. 1-4, 15 December 1998 (1998-12-15), pages 117-123, XP004154248 ISSN: 0022-0248 page 118 -page 119	1,2,15, 16,18

Information patent family members

PC 00/00951

•	_	Patent document cited in search repor	t	Publication date	Patent family member(s)	· Publication date
$\cdot \lceil$,	DD 270770	Α	09-08-1989	NONE	
		US 5414747	A	09-05-1995	NONE	







(PCT Article 36 and Rule 70)

Applicant's	or ag	ent's file reference		 .	Oca Na Na	All of Town with the last of t	
JL2428			FOR FURTHER AC	TION		ation of Transmittal of International Examination Report (Form PCT/IPEA/416)	
International application No.			International filing date (d	ay/montl	h/year)	Priority date (day/month/year)	
PCT/GB	00/0	0951	15/03/2000			16/03/1999	
Internation G01N23		ent Classification (IPC) or nat	ional classification and IPC				
Applicant		1 1 To 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1					
THE SE	CRE	TARY OF STATE FOR	DEFENCE et al.	<u> </u>			
1. This and is	intern s tran	ational preliminary exami smitted to the applicant a	nation report has been p ccording to Article 36.	repared	d by this Inte	mational Preliminary Examining Author	ity
2. This	REPO	ORT consists of a total of	8 sheets, including this	cover s	heet.		•
			, , ,				
b (:	een a see F	eport is also accompanied amended and are the basi fule 70.16 and Section 60 exes consist of a total of	is for this report and/or s 7 of the Administrative II 7	heets c	ontaining rec	n, claims and/or drawings which have ctifications made before this Authority e PCT).	
- 							
3. This r	eport	contains indications relat	ing to the following items	s:			
1	\boxtimes	Basis of the report					
11		Priority					
III	\boxtimes	Non-establishment of op	inion with regard to nov	elty, inv	entive step a	nd industrial applicability	
IV	\boxtimes	Lack of unity of invention	า				
٧	, 🔯	Reasoned statement uncitations and explanation	der Article 35(2) with reg as suporting such staten	gard to r	novelty, inver	ntive step or industrial applicability;	
Vì		Certain documents cited	d				
VII		Certain defects in the int	ernational application				
VIII		Certain observations on	the international applica	ition			
Date of sub	missic	on of the demand		Date of c	completion of the	nis report	
10/10/200	00			12.07.20	001		İ
Name and mailing address of the international preliminary examining authority:				Authorize	ed officer	THEORES MITEL	
	Euro D-80	pean Patent Office 298 Munich	annour d	Rouaul	t, P	Caramata Maria	W. EIMOLEVAN W
		+49 89 2399 - 0 Tx: 523656 6 +49 89 2399 - 4465	•	Telephor	ne No. +49 89 2	2399 2776	\$
			1				

International application No. PCT/GB00/00951

l. Basis	f th	r	port
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1.	With regard to the elements of the international application (Replacement sheets which have been furnished to the receiving Office in response to an invitation under Article 14 are referred to in this report as "originally filed" and are not annexed to this report since they do not contain amendments (Rules 70.16 and 70.17)): Description, pages:					
	1-2	9	as originally filed			
	Cla	ims, No.:				
	12-	32	as received on	27/12/2000	with letter of	20/12/2000
	1-1	1,33,34	with telefax of	18/05/2001		
	Dra	wings, sheets:				
	1/6-	-6/6	as originally filed			
2.	With lang	n regard to the lang guage in which the i	juage, all the elements marked a international application was file	above were a d, unless othe	vailable or furnished to erwise indicated under	o this Authority in the this item.
	The	se elements were a	available or furnished to this Autl	nority in the fo	ollowing language: , v	which is:
		the language of a	translation furnished for the purp	oses of the ir	nternational search (ur	nder Rule 23.1(b)).
		the language of pu	iblication of the international app	olication (unde	er Rule 48.3(b)).	
		the language of a 155.2 and/or 55.3).	translation furnished for the purp	oses of interr	national preliminary ex	amination (under Rule
3.	With regard to any nucleotide and/or amino acid sequence disclosed in the international application, the international preliminary examination was carried out on the basis of the sequence listing:					
		contained in the in	ternational application in written	form.		
		filed together with	the international application in co	omputer reada	able form.	
		furnished subsequ	ently to this Authority in written f	orm.		
		furnished subsequ	ently to this Authority in compute	er readable fo	rm.	
			the subsequently furnished writ oplication as filed has been furni		e listing does not go be	eyond the disclosure in
		The statement that listing has been fur	the information recorded in connished.	nputer readab	le form is identical to t	he written sequence

4. The amendments have resulted in the cancellation of:

International application No. PCT/GB00/00951

		the description,	pages:							
		the claims,	Nos.:							
		the drawings,	sheets:							
5. This report has been established as if (some of) the amendments had not been made, since the considered to go beyond the disclosure as filed (Rule 70.2(c)):										
		eet containing such amendments must be referred to under item 1 and annexed to this								
6.	Add	ditional observations, if necessary:								
111.	. Nor	n-establishment of o	pinion with regard to novelty, inventive step and industrial applicability							
1.	The questions whether the claimed invention appears to be novel, to involve an inventive step (to be non-obvious), or to be industrially applicable have not been examined in respect of:									
		the entire international	al application.							
	☒	claims Nos. 24.								
be	caus	e:								
		the said international application, or the said claims Nos. relate to the following subject matter which does not require an international preliminary examination (<i>specify</i>):								
			s or drawings (<i>indicate particular elements below</i>) or said claims Nos. 24 are so unclear inion could be formed (<i>specify</i>):							
		the claims, or said cla	nims Nos. are so inadequately supported by the description that no meaningful opinion							
		no international searc	th report has been established for the said claims Nos							
2.	and/	eaningful international or amino acid sequen uctions:	preliminary examination cannot be carried out due to the failure of the nucleotide ce listing to comply with the standard provided for in Annex C of the Administrative							
		the written form has n	ot been furnished or does not comply with the standard.							
		the computer readabl	e form has not been furnished or does not comply with the standard.							

IV. Lack funity finvention

1. In response to the invitation to restrict or pay additional fees the applicant has:

International application No. PCT/GB00/00951

		□ restricted the claims.									
	☐ paid additional fees.										
☐ paid additional fees under protest.											
		neither restricted nor pa	aid addi	tional fee	s.						
2.		This Authority found that the requirement of unity of invention is not complied and chose, according to Rule 68.1, not to invite the applicant to restrict or pay additional fees.									
3.	This	his Authority considers that the requirement of unity of invention in accordance with Rules 13.1, 13.2 and 13.3 is									
		complied with.									
	×	not complied with for the following reasons: see separate sheet									
4.	national application were the subject of international preliminary										
	×	all parts.									
		the parts relating to claims Nos									
V.		easoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; eations and explanations supporting such statement									
1.	Stat	tement									
	Novelty (N)		Yes: No:		4, 5, 7, 8, 14, 16, 18, 20-23, 26, 32-34 1-3, 6, 9-13, 15, 17, 19, 25, 27-31						
	Inventive step (IS)		Yes: No:	Claims Claims	4, 5, 7, 8, 14, 16, 18, 20-23, 26, 32-34						
	Indu	ustrial applicability (IA)	Yes: No:	Claims Claims	1-34						

2. Citations and explanations see separate sheet

Concerning item I:

For the below-mentioned reason, the amendments made in Claim 1 are considered to go beyond the disclosure in the international application as filed.

Concerning the integration of a portion of the diffracted curve, the original description only mentions that the "peak intensity for the layers was integrated over a window centred on the highest point of the peak" (see page 24, lines 17, 18 of the original disclosure). The wording used in new Claim 1 is, however, much more broader, since it suggests that any portion of the diffraction peak could be integrated in order to determine the relative amounts of different chemical elements. It results for example from that wording that the selected portion is not necessarily centred on the highest point of the peak, but that this portion could be located completely either right or left of the peak, which alternative is not directly and unambiguously derivable from the original disclosure.

Accordingly, the amendments made in Claim 1 have not been taken into consideration for assessing the novelty and inventive step of the subject-matter of that claim, pursuant to Rule 70.2(c).

Concerning item III:

Independent Claim 24 is totally unclear, contrary to the requirements of Article 6 PCT. It is not understood how the steps defined in that claim, and in particular which parameter, could allow for the analysis of the composition of a material.

Concerning item IV:

Since the subject-matter of independent Claim 1 is not new (see V.2 below), that claim and independent Claim 24 are not so linked as to form a single general inventive concept (Rule 13.1 PCT).

Concerning item V:

1. Reference is made to the following document: **EXAMINATION REPORT - SEPARATE SHEET**

D1: VELLING P ET AL: 'InGaP/GaAs hole barrier asymmetry determined by (002) X-ray reflections and p-type DB-RTD hole transport' JOURNAL OF CRYSTAL GROWTH, NL, NORTH-HOLLAND PUBLISHING CO. AMSTERDAM, vol. 195, no. 1-4, 15 December 1998 (1998-12-15), pages 117-123, XP004154248 ISSN: 0022-0248

2. Novelty of the subject-matter of Claim 1:

Document D1 discloses a method of determining the relative amounts of different chemical elements like In and Ga in the chemical composition of a crystalline semiconductor material.

This method comprises the following steps of:

- -- diffracting a beam of radiation off the crystalline material (see page 120, right column, last paragraph, second sentence);
- -- measuring the angle of at least one diffraction peak and the intensity of diffracted radiation at that diffraction angle (see Fig. 2b), and
- -- using a processor to determine the relative amounts of the said element in the chemical composition of the crystalline material by using values derived from the radiation scattering powers of said chemical elements and the position and intensity of said at leat one diffraction peak (see paragraph "3. X-ray diffraction analysis" and "4. Results and discussion": The structure factor that is used for simulating in D1 theoretical diffraction curves corresponding to different chemical compositions of the material under examination is known by the skilled person to be dependent upon the scattering powers of the chemical elements in that material; these simulated curves are then compared with the measured curve, see especially Fig. 2, in order to find out the curve which best fits to the measured curve; the chemical composition assumed for simulating that best curve is therefore consider to represent the actual chemical composition of said material).

Therefore, document D1 reveals a method identical to that defined in new Claim 1 of the application. Accordingly, the subject-matter of that claim lacks novelty in view of D1 and the present application does not meet the requirements of Art. 33 (2) PCT.

INTERNATIONAL PRELIMINARY

EXAMINATION REPORT - SEPARATE SHEET

It is to be noted that if the wording "window centred on the highest point of the peak" had been used in Claim 1 instead of the wording "a portion", the subjectmatter of Claim 1 would have then appeared to be novel and non-obvious with respect to the available prior art.

3. Novelty of the subject-matter of independent Claims 25, 28-31:

Since the apparatus disclosed in D1 implicitly allows to carry out all the steps of the method described in D1, the objection raised above against Claim 1 also applies to Claim 25 whose subject-matter, hence, is not novel having regard to the teachings of D1. It follows therefrom that the subject-matter of independent Claim 29 lacks novelty with respect to D1, because the programm allowing to run the apparatus of D1 is at least available in a memory (ROM or RAM) or on a hard disk, both elements being considered as being data carrier.

Furthermore, the subject-matter of independent Claims 28, 30 and 31 is not novel either, because document D1 reveals an apparatus for checking and/or analysing a wafer of a semiconductor material (see especially page 118, right column, part "2. Experimental procedures", third sentence).

Dependent Claims 2-23 and 26, 27, 32, 33, independent Claim 34: 4.

The subject-matter of Claims 2, 3, 6, 9-13, 15, 17, 19 and 27 is considered to be disclosed either implicitly or explicitly in D1 (see the above-mentioned passages of that document).

The subject-matter of Claims 4, 5, 7, 8, 14, 16, 18, 20-23, 26, 32 and 33 does not appear to involve an inventive step (Art. 33 (3) PCT, having regard to the teachings of D1 (see the above-mentioned passages of that document) and to the common knowledge of the skilled person in the technical field of X-ray analysis of semiconductor materials.

The subject-matter of independent Claim 34 is similar to that of dependent Claim 14, which is not considered to involve an inventive step, because the skilled person knowing D1 would certainly not restrict the teachings of that document to

INTERNATIONAL PRELIMINARY InternEXAMINATION REPORT - SEPARATE SHEET

International application No. PCT/GB00/00951

tertiary samples. It would namely be obvious to him that the method described in D1 could be applied to a crystalline quaternary semiconductor material as well.

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CLAIMS

- 1. A method of analysing the chemical composition of a semiconductor material comprising irradiating the semiconductor material with energy from an energy source which energy is diffracted from the semiconductor material, detecting one or more portions of the diffracted energy, and analysing the or each detected portion to obtain a parameter indicative of the intensity of the or each portion, and using knowledge of the position and/or intensity of a portion of diffracted energy to determine the chemical composition of the semiconductor.
- 2. A method of determining the relative amounts of different chemical elements E1 to En in the chemical composition of a crystalline semiconductor material, the method comprising diffracting a beam of radiation off the crystalline material and measuring the angle of at least one defraction peak and the intensity of diffracted radiation at that diffraction angle, and using a processor to determine the relative amounts of the elements E1 to En in the chemical composition of the crystalline material by using values derived from the radiation scattering powers of the elements E1 to En and the position and intensity of said at least one diffraction peak.
- 3. A method according to claim 1 or claim 2 in which the or each or some of the diffraction peaks, or the or each or some of the portions of the diffracted energy, is at a quasi-forbidden angle of diffraction from the semiconductor material.
 - 4. A method according to claim 2 in which the or each or some of the quasi-forbidden diffraction is at a (002) reflection.

- 5. A method according to claim 2 or claim 3 in which the or each or some of the quasi-forbidden diffractions is at a (006) reflection.
- 6. A method according to claim 1 or claim 2 in which the or each or some of the diffraction peaks or the or each or some of the portions of the diffracted energy is resultant from a (004) reflection.
 - 7. A method according to any preceding claim which comprises using a knowledge of the structure of the material and the possible elements present in the material to determine the chemical composition of the material.
 - 8. A method according to claim 2 or any claim dependent directly or indirectly from claim 2 in which the crystalline semiconductor material is assumed to be comprised of only a finite number of known predetermined chemical elements and the processor has operational in its processing of the measured input data and stored element scattering power values only the scattering powers for the known predetermined assumed finite number of elements that are assumed to be present.

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- 9. A method according to claim 8 in which the material is assumed to be comprised of four or less chemical elements.
- 10. A method according to any preceding claim which comprises 25 determining the composition of a layer of a material and makes use of a knowledge of the thickness of the layer, or an assumption of the thickness of the layer being analysed.

- 11. A method according to any of claims 1 to 10 which comprises determining the composition of a single layer of a material on a substrate of the material.
- 5 12. A method according to any preceding claim which comprises measuring the position of at least two diffraction peaks or at least two portions of the diffracted energy and using a knowledge of their position to determine the relative amount of chemical elements in the chemical composition of the semiconductor material.

- 13. A method according to any preceding claim which comprises measuring the intensity of diffracted beams at at least two positions or measuring the intensity of at least two portions of the diffracted energy and using this knowledge to determine the chemical composition of the semiconductor material.
- 14. A method according to any preceding claim which comprises measuring the intensity of two diffraction peaks or two portions of the diffracted energy.

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- 15. A method according to any preceding claim in which the semiconductor material is a quaternary semiconductor material.
- 16. A method according to any one of claims 1 to 14 in which the semiconductor material is a ternary semiconductor material.
 - 17. A method according to claim 15 which further comprises measuring or assuming a parameter indicative of the lattice parameter of the quaternary semiconductor material, and using this parameter and the intensity of a diffraction peak or the parameter indicative of the intensity

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to provide, in a single diffraction measurement, an estimate of the composition of the material.

- 18. A method according to any preceding claim in which the semiconductor material is a III-V semiconductor material.
 - 19. A method according to any preceding claim in which the composition of an at least partially strained semiconductor material is analysed.

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- 20. A method according to any preceding claim in which the semiconductor material is a single crystal material.
- 21. A method according to claim 1 or any claim dependent directly or indirectly from claim 1 in which the parameter is normalised.
 - 22. A method according to any preceding claim in which the percent of each chemical element of the chemical composition of the semiconductor material is analysed with an error of 0.1% or below.

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23. A method according to claim 1 or any claim dependent directly or indirectly upon claim 1 in which detection of the diffracted energy takes place at one or more detection angles, or at a range of angles around one or more detection angles.

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24. A method according to claim 1 or any claim dependent directly or indirectly upon claim 1 in which the diffracted energy is detected at one or more angles by movement of one or more detectors, or by movement or rocking of the semiconductor material.

- 25. A method according to any preceding claim which further comprises measuring a parameter indicative of the lattice parameter of the semiconductor material.
- 5 26. A method according to claim 25 which is used to analyse the composition of a buried, non-surface, layer in the semiconductor material.
- 27. A method according to any preceding claim which further comprises comparing the detected composition of the semiconductor material to a reference composition to determine if the detected composition is equal to that composition or falls within a predetermined range around the reference composition, and producing a first output if the measured composition falls within the range and a second output if the measured composition falls outside the range.

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- 28. A method of analysing the composition of an at least partially strained material comprising irradiating the material with energy from an energy source which energy is diffracted from the material, detecting one or more portions of the diffracted energy, and analysing the or each detected portion to obtain a parameter indicative of the position and/or intensity of the or each portion.
- 29. A method of analysing the composition of a material comprising irradiating the material with energy from an energy source which energy is diffracted from the material, detecting one or more portions of the diffracted energy comprising quasi-forbidden reflections, and analysing the or each detected portion to obtain a parameter indicative of the position and/or intensity of the or each portion.

30. Chemical composition analysis apparatus comprising a sample holder, a beam source, a detector or detectors, a controller, and a processor, the controller being adapted to control the beam source and detector in use so as to direct a beam of energy onto a sample held in the sample holder and detect diffracted energy at diffraction angles, the detector(s) being coupled to the processor to provide the processor in use with signals representative of the position of a diffraction peak and the intensity of the diffraction peak, and the processor being arranged such that in use it uses the detected signals, in combination with an assumption of what predetermined elements are present in the sample and the scattering power of atoms of the elements that are assumed to be present, or a factor dependent upon the scattering power of the predetermined elements, to evaluate the relative amounts of the predetermined chemical elements in the chemical composition of the sample.

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- 31. Apparatus according to claim 30 having an element selection inputter adapted to enable a user to identify to the processor which chemical elements are to be assumed to be present in the sample to be analysed, and therefore which chemical element scattering powers, or factor dependent upon the scattering powers, are to be used by the processor in determining the relative amounts of the chemical elements in the sample, the processor being adapted in use to operate with its processor on the measured input variables from the detector(s) and a subset of element scattering powers, or derived values, selected from a larger set of stored element scattering powers, or derived values, the subset being selectable by the operation of the element selection inputter.
- 32. Apparatus according to claim 30 or claim 31 in which the sample holder, beam source and detector(s) are pre-set at predetermined positions relative to each other at a relationship where for a sample of a known kind

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the or at least one detector is disposed so as to detect at a quasi-forbidden diffraction angle.

- 33. Semiconductor wafer checking apparatus comprising apparatus 5 according to any one of claims 30 to 32.
 - 34. A data carrier carrying a programme which when running on detection apparatus is adapted to enable the apparatus to perform a method of any one of Claims 1 to 29, or which when loaded into a control computer of the detection apparatus is adapted to provide the apparatus of any one of Claims 30 to 33.
 - 35. Apparatus for the analysis of the composition of a semiconductor material being arranged to operate in use in accordance with the method of any of claims 1 to 29.
 - 36. A composition measurement system arranged to analyse the composition of a semiconductor material according to any of claims 1 to 2, and to compare this to a reference or output the results of the analysis.
 - 37. A method of manufacturing a semiconductor chip comprising manufacturing a semiconductor wafer, analysing the composition of the wafer according to any one of claims 1 to 29 to test if it passes or fails a composition analysis test, and performing fabrication operations on the wafer to produce the chip if the wafer has a composition within predetermined parameters, and rejecting the wafer for further processing or fabrication operations if it has a composition outside of the predetermined parameters, rejected wafers not being subject to at least one processing step that they would have received had they passed.

38. A method according to claim 37 in which wafers that pass the compositional analysis test and/or chips produced from such wafers are accompanied by data either confirming that they passed, or data giving details of their compositional analysis.

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